

Notice of References Cited	Application/Control No. 10/648,317	Applicant(s)/Patent Under Reexamination KURODA ET AL.	
	Examiner John Ruggles	Art Unit 1756	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,236,033	05-2001	Ebbesen et al.	250/216
	B	US-2005/0026047	02-2005	Yang, Chin Cheng	430/005
	C	US-6,171,730	01-2001	Kuroda et al.	430/5
	D	US-6,187,482	02-2001	Kuroda et al.	430/5
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	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

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	U	Alkaisi, M. M. et al., "Sub-diffraction-limited patterning using evanescent near-field optical lithography", (1999) Applied Physics Letters, Vol. 75, No.22, Pages 3560-3562
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.